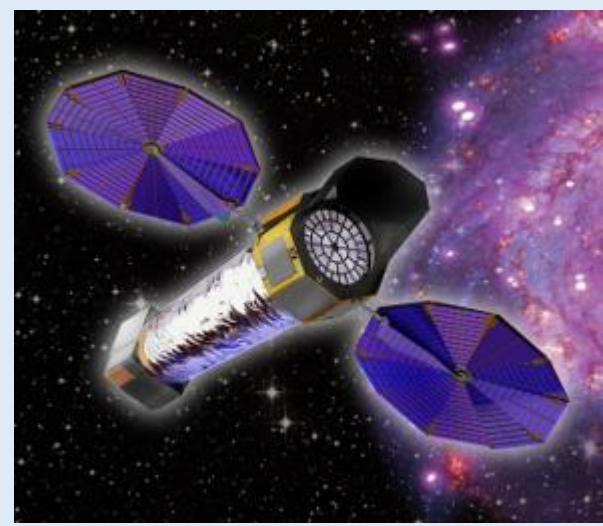


Prototype Magnetic Calorimeter Arrays with Buried Wiring for the Lynx X-ray Microcalorimeter

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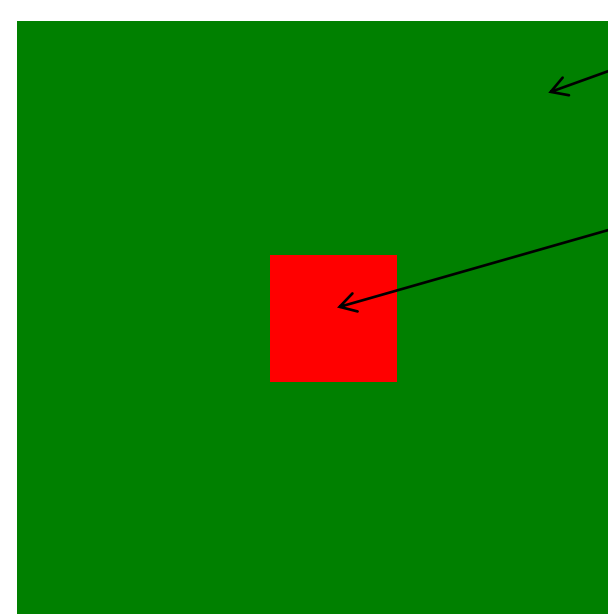


Introduction

- Lynx is a large mission concept under development by NASA for the Astro 2020 Decadal survey
- One of the key Lynx instruments is an imaging spectrometer called the Lynx X-ray Microcalorimeter (LXM) which comprises of a very large detector array with > 100K pixels

- Metallic magnetic calorimeter (MMC) technology is a leading contender for detectors for the LXM
- MMCs can be used to measure the energy of individual X-ray photons with high precision by sensing changes in the magnetic susceptibility of a paramagnetic metal film (Au:Er) as its temperature rises in response to the absorbed photon energy

LXM array baseline configuration

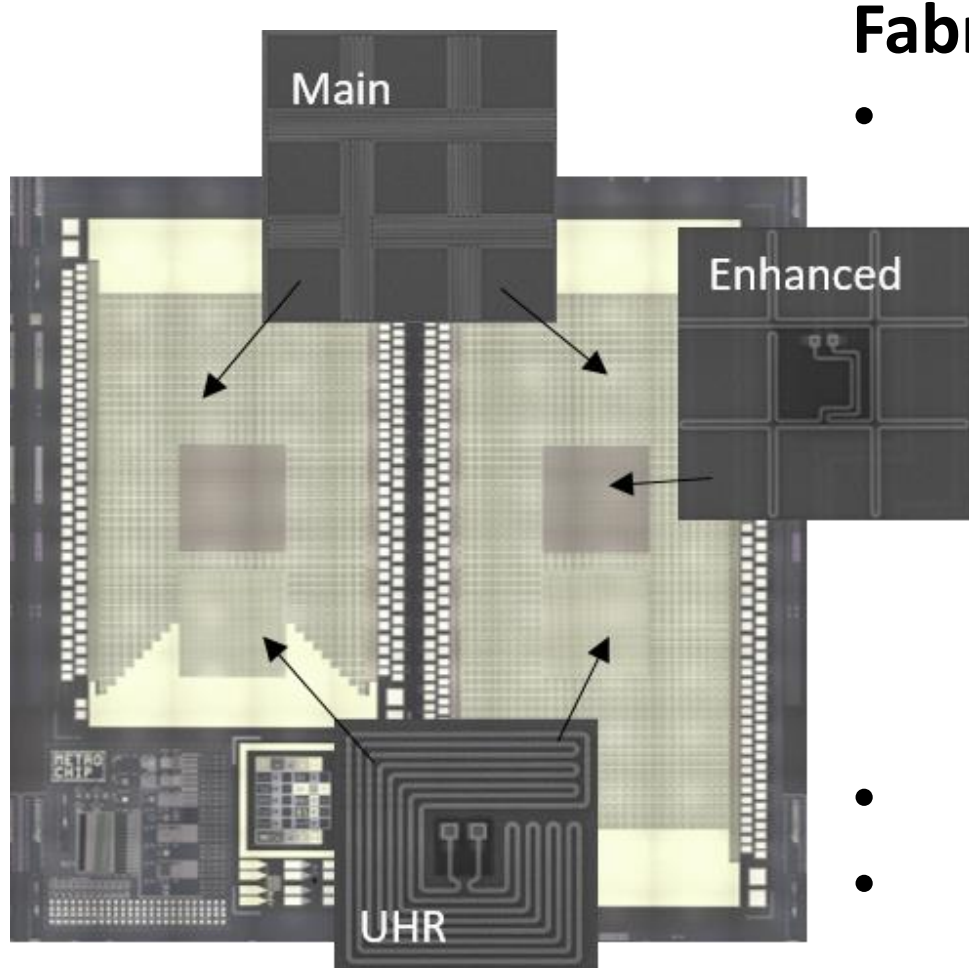


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| Main array <ul style="list-style-type: none"> 1" pixels (50 μm), 5' FOV, 5x5 hydra $\Delta E \sim 3$ eV Up to 7 keV 86400 pixels |
| Enhanced array <ul style="list-style-type: none"> 0.5" pixels (25 μm), 1' FOV, 5x5 hydra $\Delta E = 2$ eV Up to 7 keV 12800 pixels |
| UHR array <ul style="list-style-type: none"> 1" pixels (50 μm), 1' FOV $\Delta E = 0.3$ eV Up to 0.8 keV 3600 pixels |

Motivation

- Design and fabrication challenges for large size arrays
 - As array size increases, stray inductance of the wiring increases both between pixels and in the fanout to amplifiers
- Routing of wiring between pixels and readout, on a planar scheme, becomes technologically challenging due to requirements of low inductance, low crosstalk, high critical currents and high yield
- MMCs can be scaled to large array sizes by
 - Maximizing sensor inductance by decreasing sensor meander coil pitch
 - Maximizing magnetic coupling by scaling sensor (Au:Er) and sensor insulator thickness with pitch
 - Maximizing Nb thickness with pitch in order to keep sufficient critical current/width
- Buried layers can be used to achieve large scale, high density wiring
 - Well suited for connecting thousands of pixels on a large focal plane to readout chips
 - Planarization allows top surface of wafer to be exclusively available for pixels and heat sinking, opening up the possibility for new pixel geometries
 - Can alleviate crosstalk between high density, fine pitch wiring

MMC Arrays with Four Buried Nb Layers



Fabrication Summary

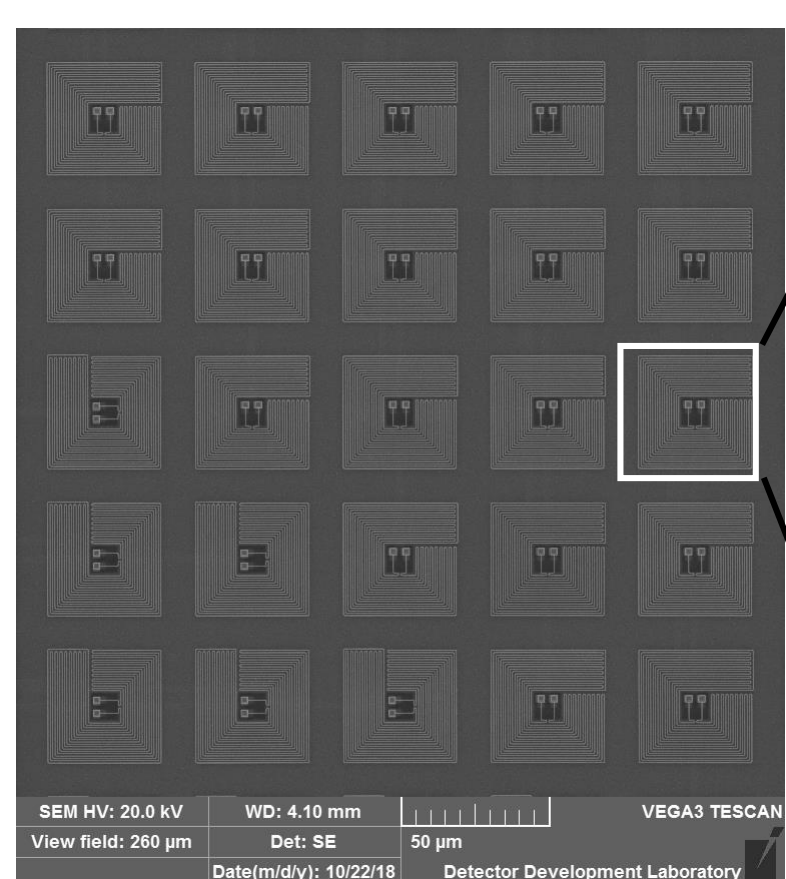
- All buried wiring and sensor meander coil layers are processed as follows
 - Nb deposition by dc magnetron sputtering
 - Patterning of Nb by deep UV (DUV) lithography (248 nm) and plasma etch
 - SiO₂ interlayer dielectric (ILD) deposition by PECVD
 - Chemical Mechanical Planarization of ILD to desired thickness
 - Patterning of ILD by DUV lithography and plasma etch
- MMC sensor (Au:Er) deposition by sputtering and patterning by lift-off
- Au thermalization layer deposition by e-beam evaporation and patterning by lift-off
- Au hydra link deposition by e-beam evaporation and patterning by lift-off
- Au heat sink deposition by e-beam evaporation and patterning by lift-off
- Stems electroplating through photoresist mold on Au seed layer
- Absorbers electroplating and etch by ion milling

Fabricating High Inductance MMCs

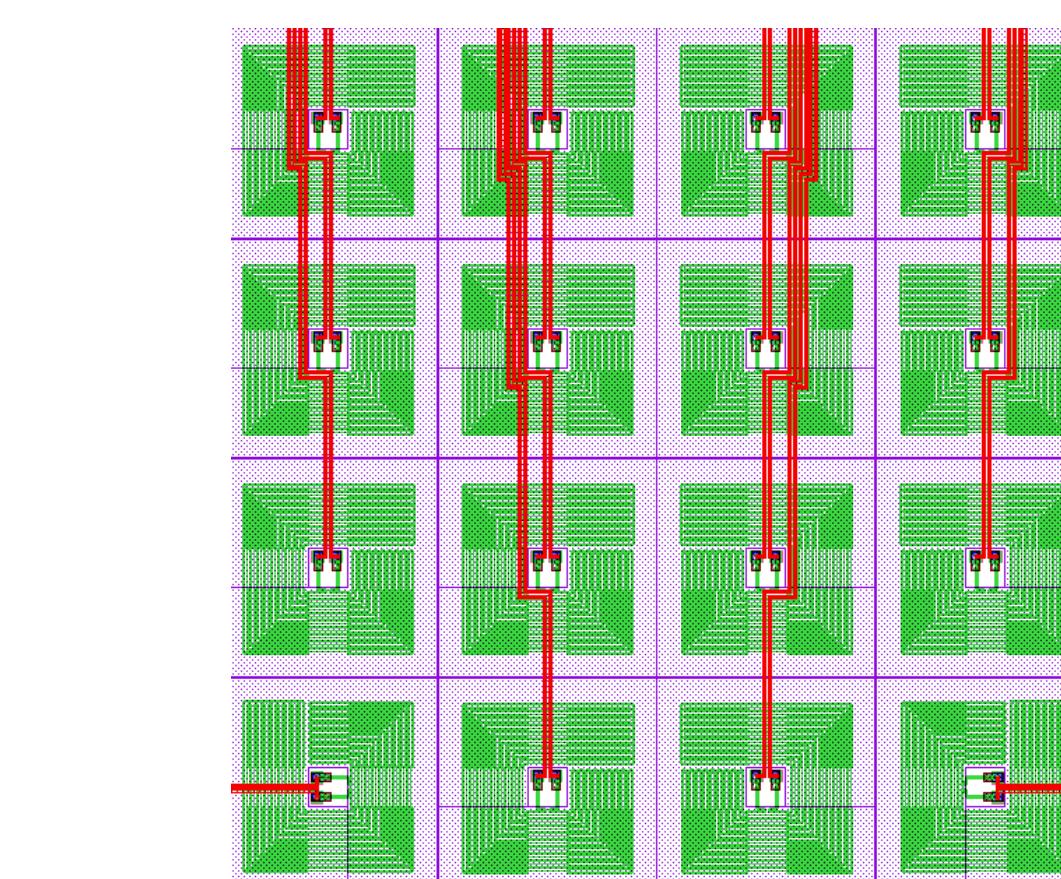
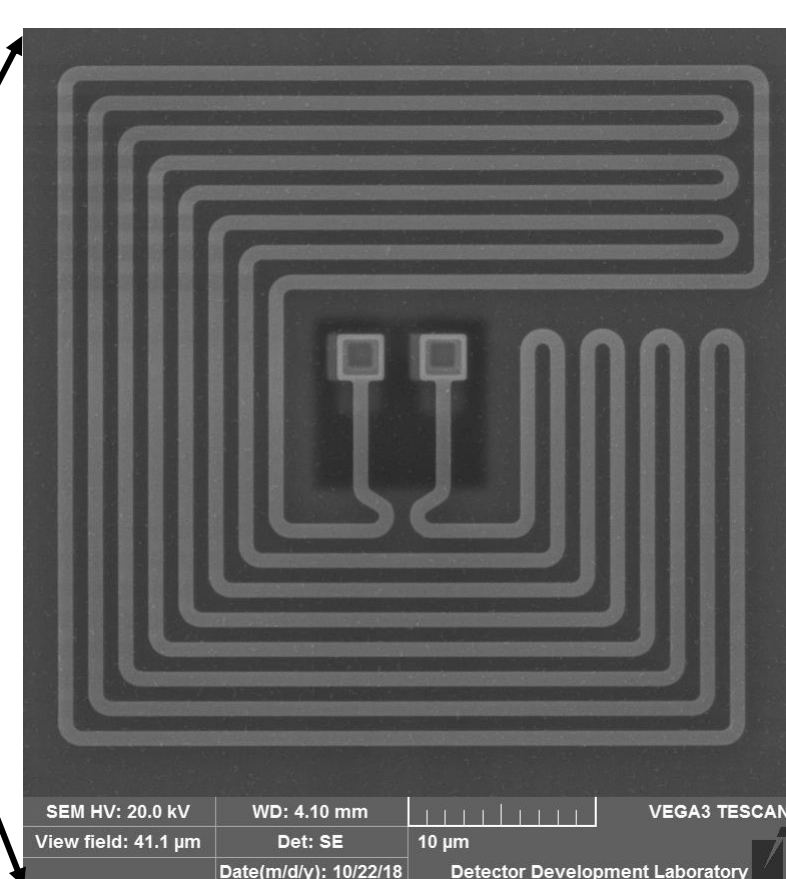
- Sensor meander coil pitch is reduced to 800 nm to increase sensor inductance
- To maintain good magnetic coupling with the reduced pitch, thickness of Au:Er is scaled to 128 nm
- To maintain a large critical current per unit width in the wiring and the sensor meander coils, Nb is anisotropically etched to produce vertical edges, resulting in an approximately square cross section
- By using multiple layers of buried wiring, larger wiring linewidths are maintained, resulting in a decrease in the wiring inductance

UHR array

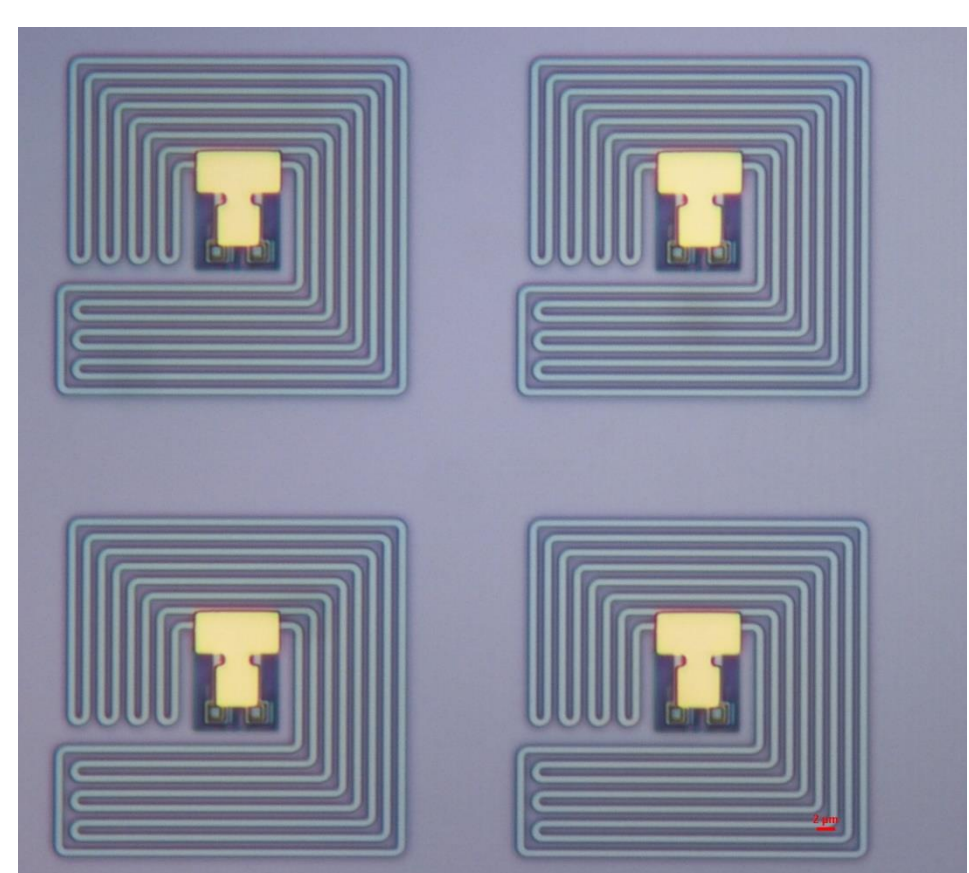
- Square annulus shaped sensor with non-hydra design
- Superconducting vias at the center of the sensor connect sensor meander coils on the topmost Nb layer to twin microstrip wiring on the bottom most Nb layer
- Au thermal link connects sensor to absorber stem in order to control size of slew rate at readout



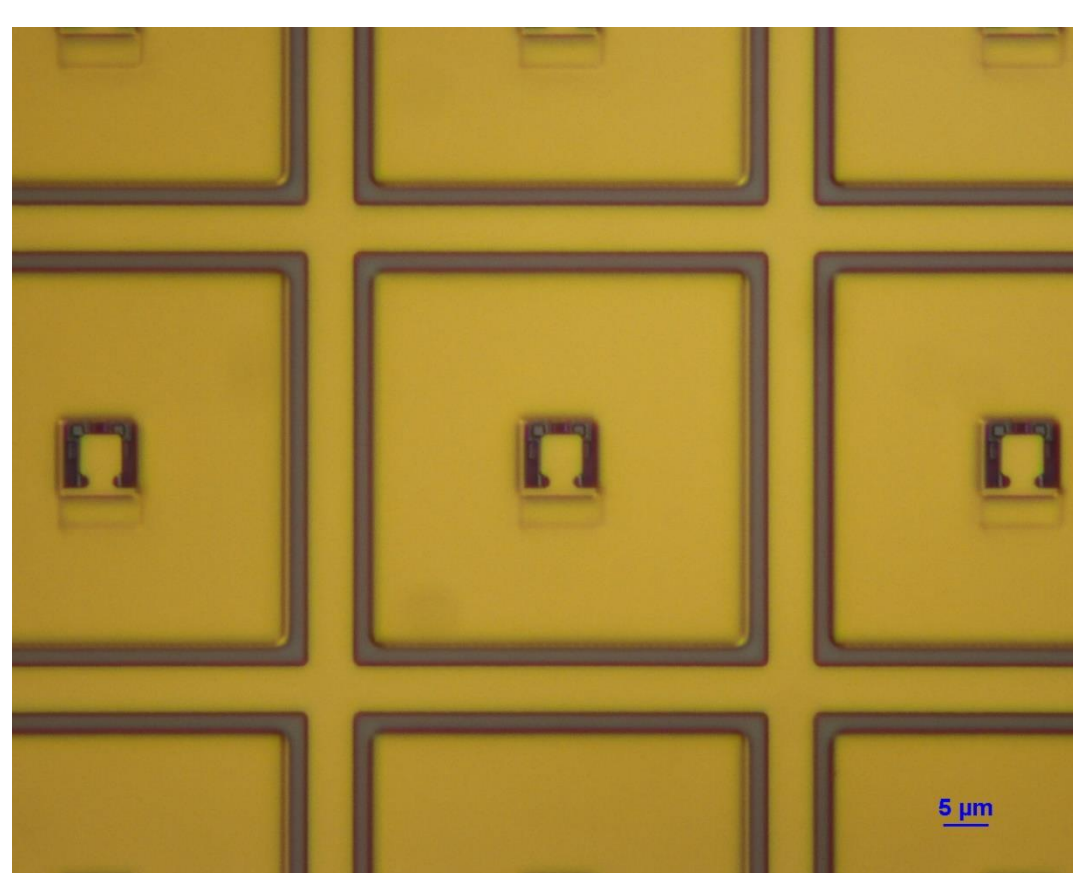
UHR array of Nb sensor meander coils



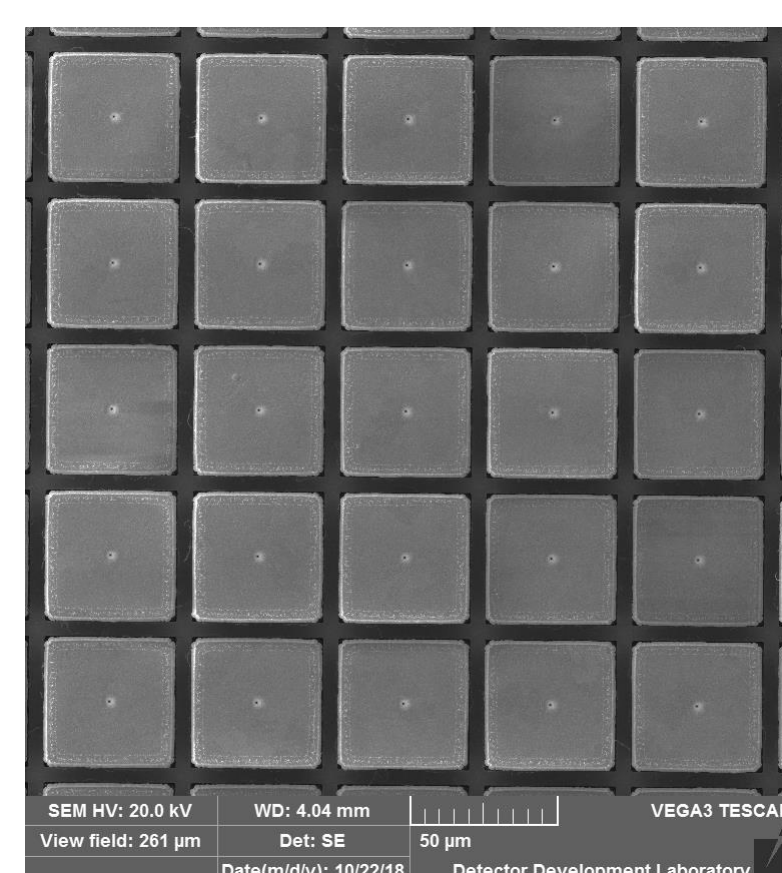
Multilayer buried wiring employed to fabricate UHR pixels: Top Nb sensor meander layer (green) is connected through two intermediate metal layers to bottom wiring (red)



After addition of Au hydra links



With Au:Er sensor and Au heat sinking grid deposited



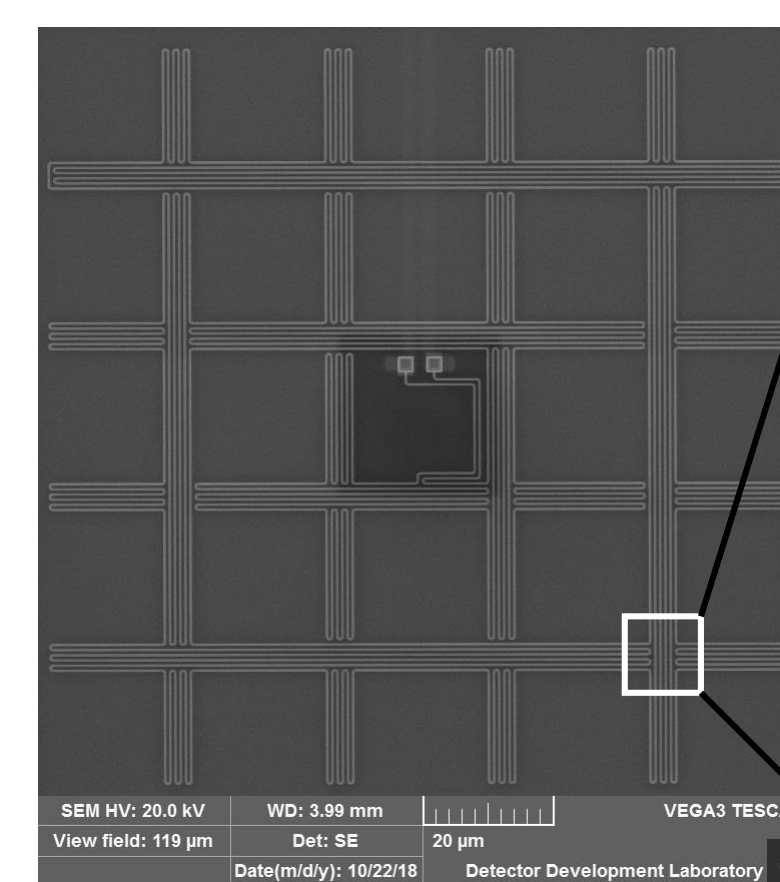
50 μ m x 50 μ m sized individual Au absorbers suspended over UHR pixels

Prototype Highlights

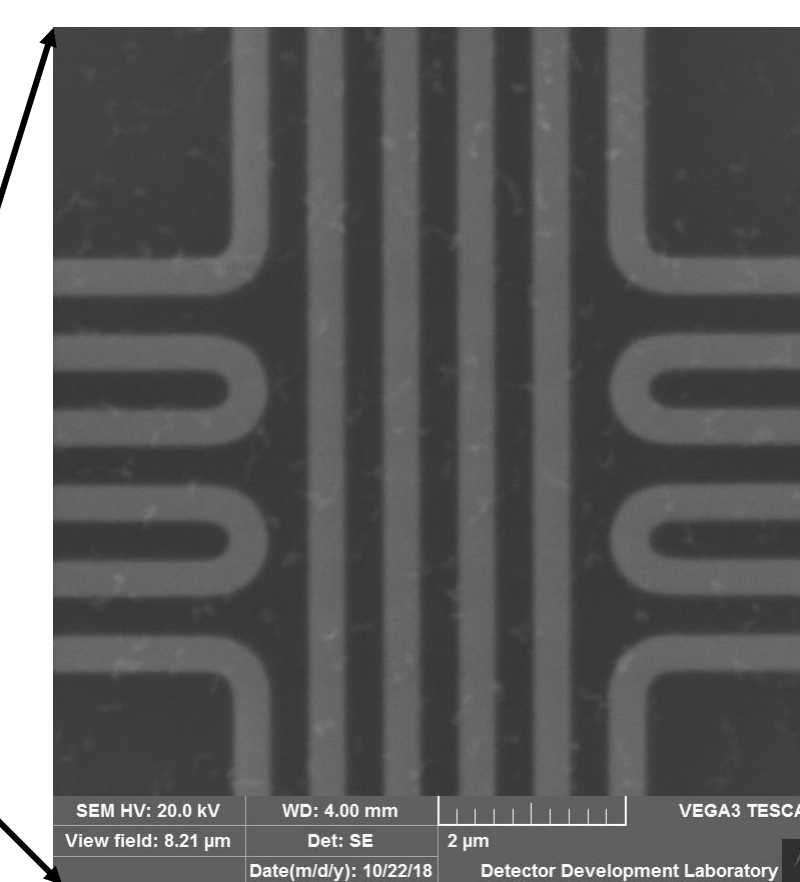
- 55800 pixels thermally linked to 5688 sensors
- 4 buried Nb layers
 - high yield, low inductance, high density wiring
 - reduced cross-talk through the use of shielding ground planes
 - precludes need for aggressive packing of wiring on one layer by allowing the fanout of wires from sub-arrays under Main array pixels
- Multi-absorber sensors

Main and Enhanced arrays

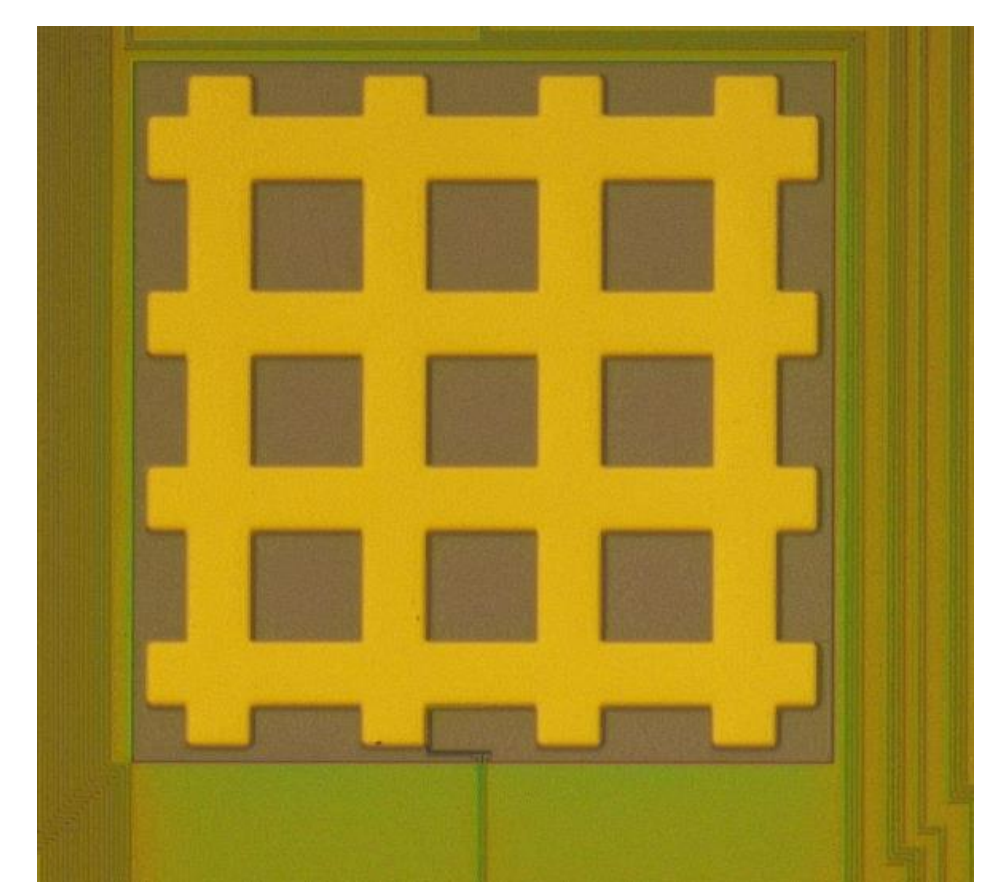
- Arrays of waffle shaped sensors in a 5 x 5 hydra configuration



Nb sensor meander coil

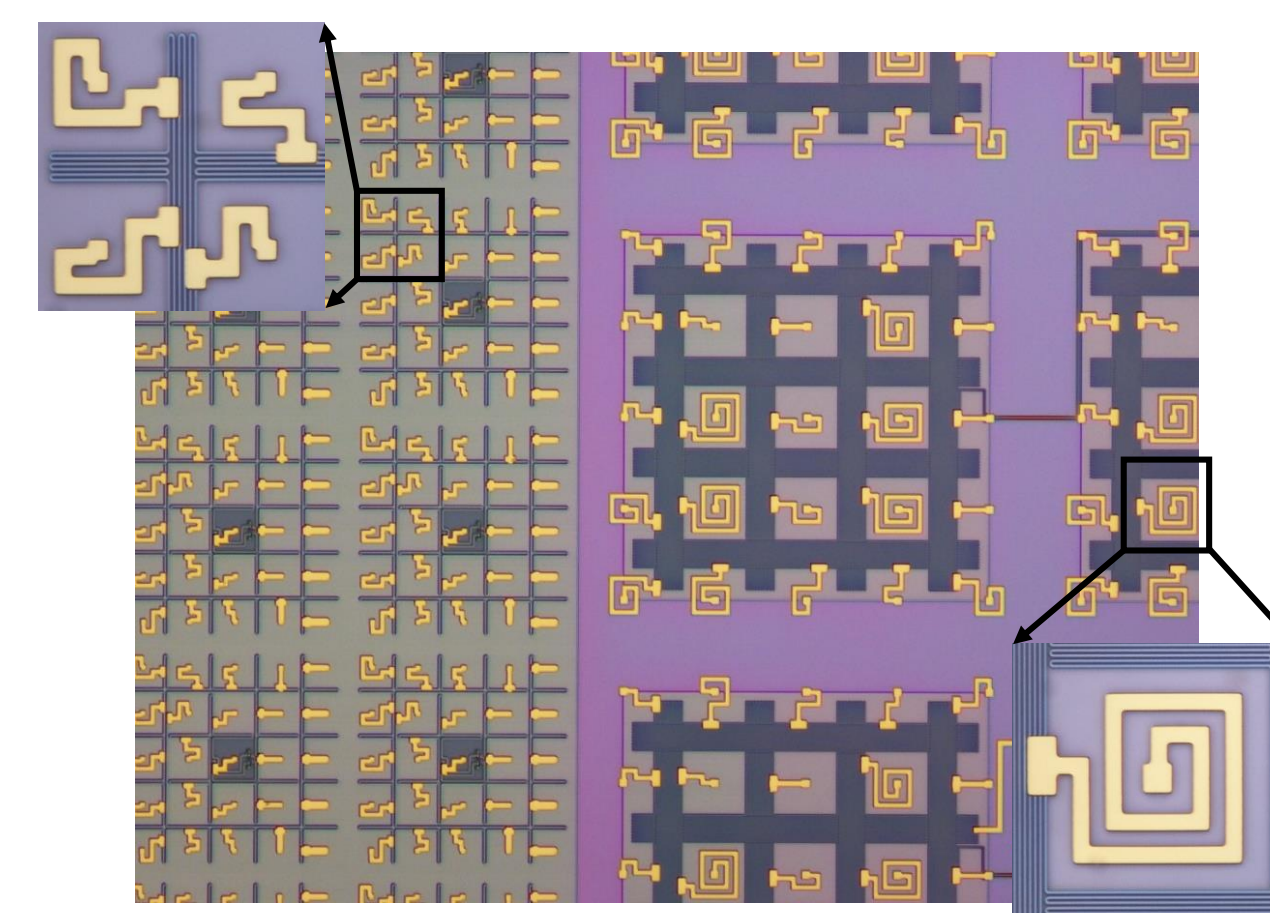


800 nm pitch sensor meander coil

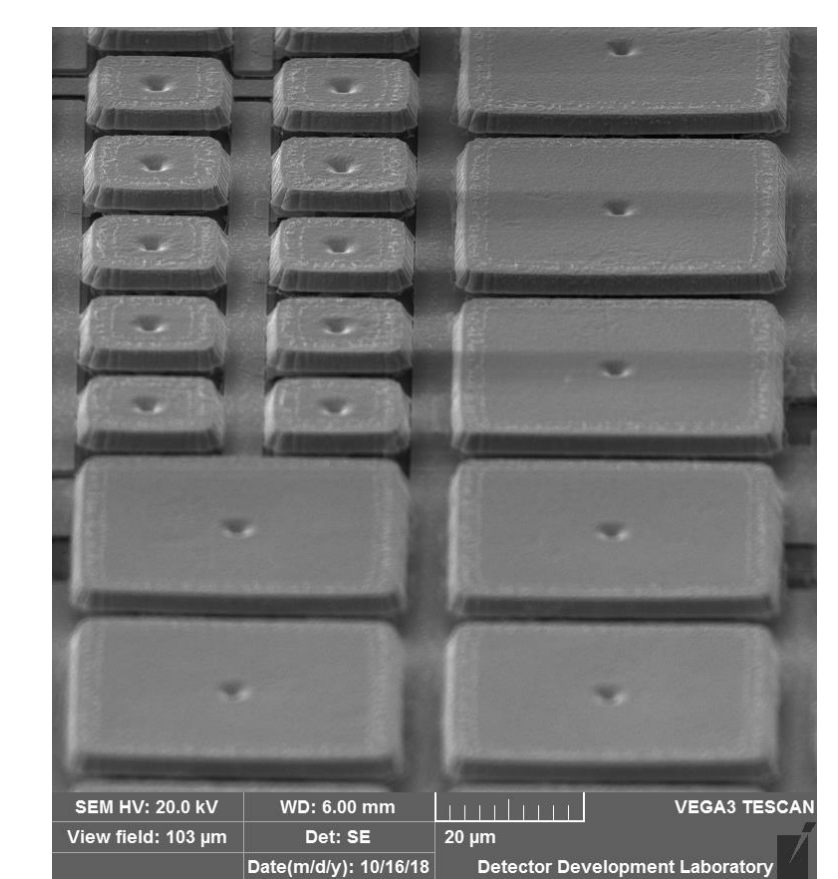


Waffle shaped Au:Er sensor over sensor meander coil

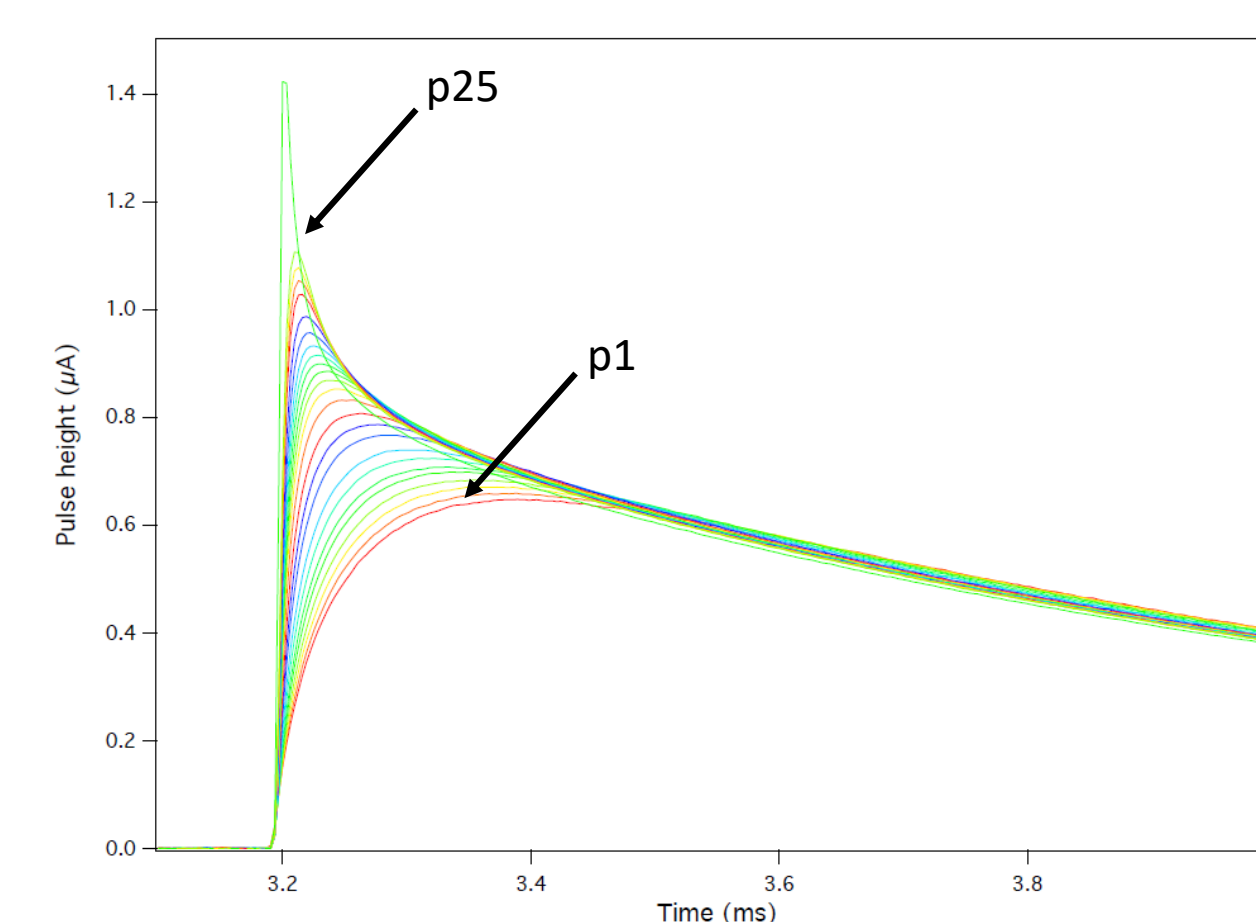
- Main array sensor meander coils and twin microstrip wiring are patterned on top Nb layer
- Enhanced array sensor meander coils on topmost Nb layer are connected through superconducting vias to twin microstrip wiring on the bottom most Nb layer
- Hydra design allows 25 different pixels to be read using a single sensor. 25 absorbers are coupled to a single sensor through Au thermal (hydra) links of varied thermal conductance.
- Au absorber is anchored in place by a central Au stem



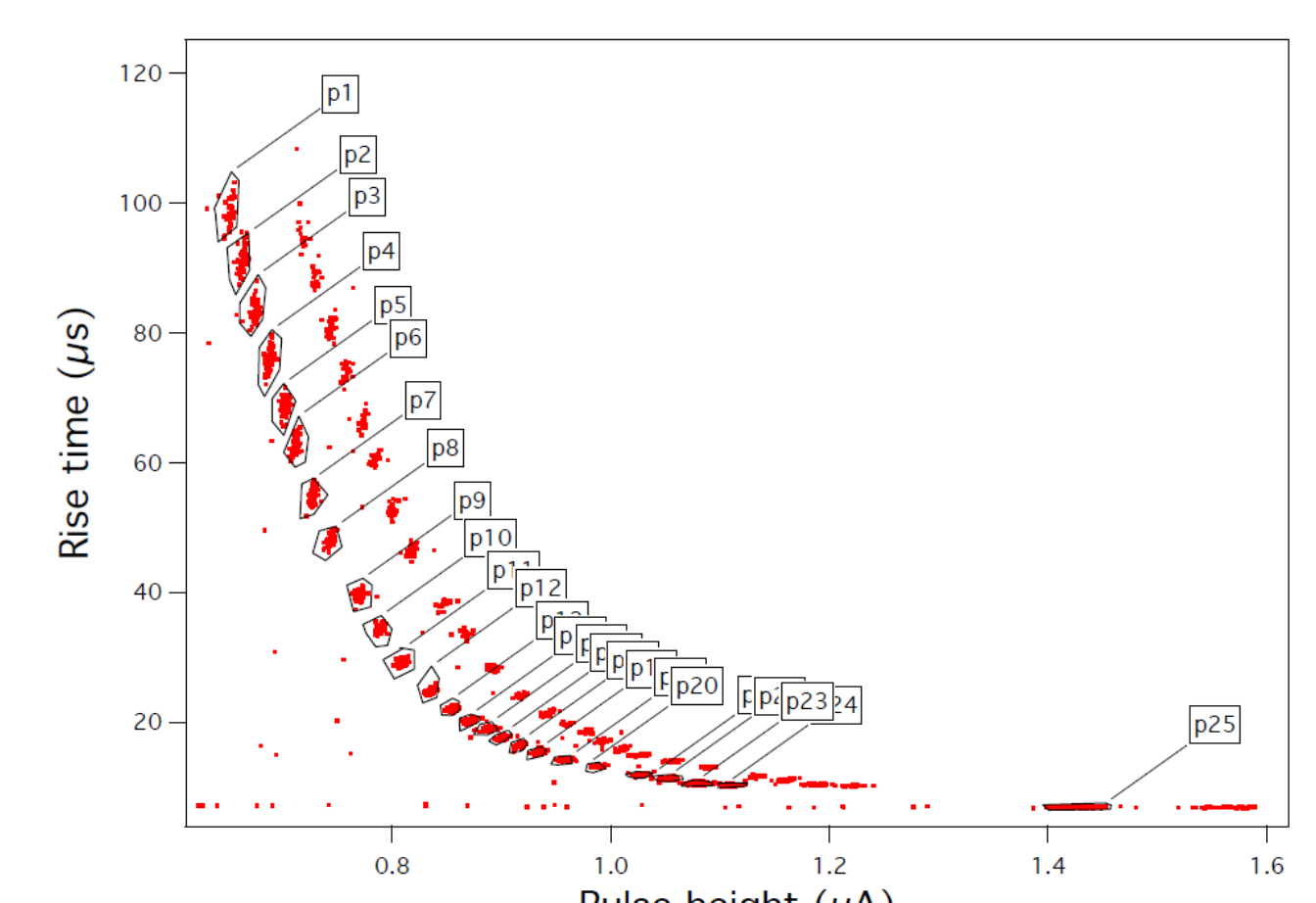
Enhanced array (left) and Main array (right) hydra link design



20 μ m x 20 μ m hydra absorbers for enhanced array pixels (top left), 50 μ m x 50 μ m hydra absorbers for Main array pixels (bottom and right)



Measured averaged pulse shapes for 25 individual pixels of a Main array hydra, measured at 50 mK and with 15 mA of current trapped in meander coil



Position discrimination of pixels in a Main array hydra as indicated by 25 clearly separated groups